

Ti-Nb ALLOY SPUTTERING TARGET AND PRODUCTION METHOD THEREOF

ABSTRACT

5

Provided is a Ti-Nb alloy sputtering target containing 0.1 to 30 at% of Nb, the remainder of Ti and unavoidable impurities; and the Ti-Nb alloy sputtering target is characterized by having an oxygen content of 400 wtppm or less. Since the target in the present disclosure has a favorable surface texture with a low oxygen content and is readily processable due to the low hardness of the target, the Ti-Nb alloy sputtering target yields a superior effect of being able to suppress the generation of particles during sputtering.

10

15